IN THE CLAIMS

Please amend the claims as follows:

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- 3. A method as claimed in claim 1, characterized in that use is made of gratings for the substrate alignment mark, the additional alignment mark and the reference alignment mark.
- 4. A method as claimed in claim 1, characterized in that the additional alignment mark is a latent mark.

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6. A method as claimed in claim 1, characterized in that it is based on the on-axis alignment principle.

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- 8. A method as claimed in claim 1, characterized in that it is based on the off-axis alignment principle.
- 9. A method of manufacturing devices in at least one layer of a substrate, which method comprises at least one set of the following successive steps:
- aligning a mask provided with a mask pattern comprising pattern features corresponding to a device feature to be configured in said layer;
- imaging, by means of projection radiation, the mask pattern in a radiation-sensitive layer on the substrate, and